L Number	Hits	Search Text	DB	Time stamp
1	31	((((((magnetic adj head) or (magneto adj	USPAT;	2004/08/09 18:08
		resistive) or magnetoresistive or	US-PGPUB;	
		magnetophotoresistive or (magneto adj	EPO; JPO;	
		photoresistive) or (giant adj magneto\$15)	IBM TDB	
		or (GMR same magneto\$15)).ti,ab.) and	_	
		(resist or photoresist or photopolymer\$7		
		or photoimag\$5)) and ((ash\$3 or (ash adj		
		treat\$4) or etch\$3 or narrow\$3 or shrink\$3		
		or shrunk\$3 or contract\$3 or small\$3 or		
	İ	littl\$3 or reduc\$3 or decreas\$3 or slim\$4		
		or trim\$4 or less\$5 or tight\$4) same		
		(resist or photoresist or imag\$3 or		
		pattern\$3))) and ((resist or photoresist		
	ļ	on impact on not town (2) name //awwent on	•	·
		or imag\$3 or pattern\$3) same ((oxygen or		
	1	"O" or "O.sub.2") and (fluorine or		
		fluoride or "F" or "F.sub.2" or ((nitrogen		
		or "N" or "N.sub.2") and (hydrogen or "H"		
		or "H.sub.2")))))) and (((mill\$3 or ion		
		adj beam or FIB or RIE or ion adj etch\$3		
	1	or sputter\$3) or (lift adj off or liftoff		
		or remov\$3 or etchback or etch\$3 adj		
		back)) near5 (resist or photoresist or		
		imag\$3 or pattern\$3))) and ((heat\$3 or		
		bak\$3) with (resist or photoresist or		
		imag\$3 or pattern\$3))		
2	11	(((((magnetic adj head) or (magneto adj	USPAT;	2004/08/09 18:09
		resistive) or magnetoresistive or	US-PGPUB;	2001,00,03 10.03
		magnetophotoresistive or (magneto adj	EPO; JPO;	
		photoresistive) or (giant adj magneto\$15)	IBM TDB	
		or (GMR same magneto\$15)).ti,ab.) and	1011_100	
		(resist or photoresist or photopolymer\$7		
		or photoimag\$5)) and ((ash\$3 or (ash adj		
		treat\$4) or etch\$3 or narrow\$3 or shrink\$3		
		or shrunk\$3 or contract\$3 or small\$3 or		
		littl\$3 or reduc\$3 or decreas\$3 or slim\$4		
		or trim\$4 or less\$5 or tight\$4) same		
		(resist or photoresist or imag\$3 or		
		<pre>pattern\$3))) and ((resist or photoresist</pre>		
		or imag\$3 or pattern\$3) same ((oxygen or		
		"O" or "O.sub.2") and (fluorine or		
		fluoride or "F" or "F.sub.2" or ((nitrogen		
		or "N" or "N.sub.2") and (hydrogen or "H"		
		or "H.sub.2")))))) not ((((((magnetic adj		
		head) or (magneto adj resistive) or		
		magnetoresistive or magnetophotoresistive		
	1	or (magneto adj photoresistive) or (giant		
		adj magneto\$15) or (GMR same		
		magneto\$15)).ti,ab.) and (resist or		
		photoresist or photopolymer\$7 or		.
		photoimag\$5)) and ((ash\$3 or (ash adj		
		treat\$4) or etch\$3 or narrow\$3 or shrink\$3		
		or shrunk\$3 or contract\$3 or small\$3 or		
		littl\$3 or reduc\$3 or decreas\$3 or slim\$4		
		or trimed or logger or timbted and		
		or trim\$4 or less\$5 or tight\$4) same		
	.	(resist or photoresist or imag\$3 or		
		pattern\$3))) and ((resist or photoresist		
		or imag\$3 or pattern\$3) same ((oxygen or		
		"O" or "O.sub.2") and (fluorine or		-
i		fluoride or "F" or "F.sub.2" or ((nitrogen		
		or UNU or UN sub 2U) and (budmager or UUU	ı	j l
		or "N" or "N.sub.2") and (hydrogen or "H"]
		or "H.sub.2")))))) and (((mill\$3 or ion		
		or "H.sub.2")))))) and (((mill\$3 or ion adj beam or FIB or RIE or ion adj etch\$3 or sputter\$3) or (lift adj off or liftoff		
		or "H.sub.2")))))) and (((mill\$3 or ion adj beam or FIB or RIE or ion adj etch\$3		
		or "H.sub.2")))))) and (((mill\$3 or ion adj beam or FIB or RIE or ion adj etch\$3 or sputter\$3) or (lift adj off or liftoff		

3	4	(((((magnetic adj head) or (magneto adj	USPAT;	2004/08/09 18:0
		resistive) or magnetoresistive or magnetophotoresistive or (magneto adj	US-PGPUB; EPO; JPO;	
		photoresistive) or (giant adj magneto\$15)	IBM TDB	
		or (GMR same magneto\$15)).ti,ab.) and	IBII_IBB	
		(resist or photoresist or photopolymer\$7		
		or photoimag\$5)) and ((ash\$3 or (ash adj		
		treat\$4) or etch\$3 or narrow\$3 or shrink\$3		
		or shrunk\$3 or contract\$3 or small\$3 or		
		littl\$3 or reduc\$3 or decreas\$3 or slim\$4		
		or trim\$4 or less\$5 or tight\$4) same		
		(resist or photoresist or imag\$3 or		
		<pre>pattern\$3))) not (((((magnetic adj head)</pre>		
		or (magneto adj resistive) or		
		magnetoresistive or magnetophotoresistive		
		or (magneto adj photoresistive) or (giant		
		adj magneto\$15) or (GMR same		
		magneto\$15)).ti,ab.) and (resist or		
		photoresist or photopolymer\$7 or		
		photoimag\$5)) and ((ash\$3 or (ash adj	İ	
		treat\$4) or etch\$3 or narrow\$3 or shrink\$3 or shrunk\$3 or contract\$3 or small\$3 or		
		littl\$3 or reduc\$3 or decreas\$3 or slim\$4		
		or trim\$4 or less\$5 or tight\$4) same		
		(resist or photoresist or imag\$3 or		
		pattern\$3))) and ((resist or photoresist		
		or imag\$3 or pattern\$3) same ((oxygen or		
		"O" or "O.sub.2") and (fluorine or		
		fluoride or "F" or "F.sub.2" or ((nitrogen		
		or "N" or "N.sub.2") and (hydrogen or "H"		
		or "H.sub.2")))))) and	1	
		(polymethylglutarimide)		
:	0	(((((magnetic adj head) or (magneto adj	USPAT;	2004/08/09 18:10
		resistive) or magnetoresistive or	US-PGPUB;]
		magnetophotoresistive or (magneto adj	EPO; JPO;	
		photoresistive) or (giant adj magneto\$15)	IBM_TDB	
		or (GMR same magneto\$15)).ti,ab.) and	Ì	
	1	<pre>(resist or photoresist or photopolymer\$7 or photoimag\$5)) and ((ash\$3 or (ash adj</pre>		
	1	treat\$4) or etch\$3 or narrow\$3 or shrink\$3		
		or shrunk\$3 or contract\$3 or small\$3 or		
		littl\$3 or reduc\$3 or decreas\$3 or slim\$4		
		or trim\$4 or less\$5 or tight\$4) same		
		(resist or photoresist or imag\$3 or		
		<pre>pattern\$3))) not (((((magnetic adj head)</pre>		1
	i .			
		or (magneto adj resistive) or		
		magnetoresistive or magnetophotoresistive		
		magnetoresistive or magnetophotoresistive or (magneto adj photoresistive) or (giant		
		magnetoresistive or magnetophotoresistive or (magneto adj photoresistive) or (giant adj magneto\$15) or (GMR same		
		magnetoresistive or magnetophotoresistive or (magneto adj photoresistive) or (giant adj magneto\$15) or (GMR same magneto\$15)).ti,ab.) and (resist or		
		magnetoresistive or magnetophotoresistive or (magneto adj photoresistive) or (giant adj magneto\$15) or (GMR same magneto\$15)).ti,ab.) and (resist or photoresist or photopolymer\$7 or		
		magnetoresistive or magnetophotoresistive or (magneto adj photoresistive) or (giant adj magneto\$15) or (GMR same magneto\$15)).ti,ab.) and (resist or photoresist or photopolymer\$7 or photoimag\$5)) and ((ash\$3 or (ash adj		
·		magnetoresistive or magnetophotoresistive or (magneto adj photoresistive) or (giant adj magneto\$15) or (GMR same magneto\$15)).ti,ab.) and (resist or photoresist or photopolymer\$7 or photoimag\$5)) and ((ash\$3 or (ash adj treat\$4) or etch\$3 or narrow\$3 or shrink\$3		
·		magnetoresistive or magnetophotoresistive or (magneto adj photoresistive) or (giant adj magneto\$15) or (GMR same magneto\$15)).ti,ab.) and (resist or photoresist or photopolymer\$7 or photoimag\$5)) and ((ash\$3 or (ash adj treat\$4) or etch\$3 or narrow\$3 or shrink\$3 or shrunk\$3 or small\$3 or		
		magnetoresistive or magnetophotoresistive or (magneto adj photoresistive) or (giant adj magneto\$15) or (GMR same magneto\$15)).ti,ab.) and (resist or photoresist or photopolymer\$7 or photoimag\$5)) and ((ash\$3 or (ash adj treat\$4) or etch\$3 or narrow\$3 or shrink\$3 or shrunk\$3 or contract\$3 or small\$3 or littl\$3 or reduc\$3 or decreas\$3 or slim\$4		
		magnetoresistive or magnetophotoresistive or (magneto adj photoresistive) or (giant adj magneto\$15) or (GMR same magneto\$15)).ti,ab.) and (resist or photoresist or photopolymer\$7 or photoimag\$5)) and ((ash\$3 or (ash adj treat\$4) or etch\$3 or narrow\$3 or shrink\$3 or shrunk\$3 or contract\$3 or small\$3 or littl\$3 or reduc\$3 or decreas\$3 or slim\$4 or trim\$4 or less\$5 or tight\$4) same		
		magnetoresistive or magnetophotoresistive or (magneto adj photoresistive) or (giant adj magneto\$15) or (GMR same magneto\$15)).ti,ab.) and (resist or photoresist or photopolymer\$7 or photoimag\$5)) and ((ash\$3 or (ash adj treat\$4) or etch\$3 or narrow\$3 or shrink\$3 or shrunk\$3 or contract\$3 or small\$3 or littl\$3 or reduc\$3 or decreas\$3 or slim\$4 or trim\$4 or less\$5 or tight\$4) same (resist or photoresist or imag\$3 or		
		magnetoresistive or magnetophotoresistive or (magneto adj photoresistive) or (giant adj magneto\$15) or (GMR same magneto\$15)).ti,ab.) and (resist or photoresist or photopolymer\$7 or photoimag\$5)) and ((ash\$3 or (ash adj treat\$4) or etch\$3 or narrow\$3 or shrink\$3 or shrunk\$3 or contract\$3 or small\$3 or littl\$3 or reduc\$3 or decreas\$3 or slim\$4 or trim\$4 or less\$5 or tight\$4) same (resist or photoresist or imag\$3 or pattern\$3))) and ((resist or photoresist		
		magnetoresistive or magnetophotoresistive or (magneto adj photoresistive) or (giant adj magneto\$15) or (GMR same magneto\$15)).ti,ab.) and (resist or photoresist or photopolymer\$7 or photoimag\$5)) and ((ash\$3 or (ash adj treat\$4) or etch\$3 or narrow\$3 or shrink\$3 or shrunk\$3 or contract\$3 or small\$3 or littl\$3 or reduc\$3 or decreas\$3 or slim\$4 or trim\$4 or less\$5 or tight\$4) same (resist or photoresist or imag\$3 or pattern\$3))) and ((resist or photoresist or imag\$3 or pattern\$3) same ((oxygen or		
		magnetoresistive or magnetophotoresistive or (magneto adj photoresistive) or (giant adj magneto\$15) or (GMR same magneto\$15)).ti,ab.) and (resist or photoresist or photopolymer\$7 or photoimag\$5)) and ((ash\$3 or (ash adj treat\$4) or etch\$3 or narrow\$3 or shrink\$3 or shrunk\$3 or contract\$3 or small\$3 or littl\$3 or reduc\$3 or decreas\$3 or slim\$4 or trim\$4 or less\$5 or tight\$4) same (resist or photoresist or imag\$3 or pattern\$3))) and ((resist or photoresist or imag\$3 or pattern\$3)) same ((oxygen or "O" or "O.sub.2") and (fluorine or		
		magnetoresistive or magnetophotoresistive or (magneto adj photoresistive) or (giant adj magneto\$15) or (GMR same magneto\$15)).ti,ab.) and (resist or photoresist or photopolymer\$7 or photoimag\$5)) and ((ash\$3 or (ash adj treat\$4) or etch\$3 or narrow\$3 or shrink\$3 or shrunk\$3 or contract\$3 or small\$3 or littl\$3 or reduc\$3 or decreas\$3 or slim\$4 or trim\$4 or less\$5 or tight\$4) same (resist or photoresist or imag\$3 or pattern\$3)) and ((resist or photoresist or imag\$3 or pattern\$3)) and (fluorine or "O" or "O.sub.2") and (fluorine or fluoride or "F" or "F.sub.2" or ((nitrogen		
		magnetoresistive or magnetophotoresistive or (magneto adj photoresistive) or (giant adj magneto\$15) or (GMR same magneto\$15)).ti,ab.) and (resist or photoresist or photopolymer\$7 or photoimag\$5)) and ((ash\$3 or (ash adj treat\$4) or etch\$3 or narrow\$3 or shrink\$3 or shrunk\$3 or contract\$3 or small\$3 or littl\$3 or reduc\$3 or decreas\$3 or slim\$4 or trim\$4 or less\$5 or tight\$4) same (resist or photoresist or imag\$3 or pattern\$3))) and ((resist or photoresist or imag\$3 or pattern\$3)) same ((oxygen or "O" or "O.sub.2") and (fluorine or		
		magnetoresistive or magnetophotoresistive or (magneto adj photoresistive) or (giant adj magneto\$15) or (GMR same magneto\$15)).ti,ab.) and (resist or photoresist or photopolymer\$7 or photoimag\$5)) and ((ash\$3 or (ash adj treat\$4) or etch\$3 or narrow\$3 or shrink\$3 or shrunk\$3 or contract\$3 or small\$3 or littl\$3 or reduc\$3 or decreas\$3 or slim\$4 or trim\$4 or less\$5 or tight\$4) same (resist or photoresist or imag\$3 or pattern\$3)) and ((resist or photoresist or imag\$3 or pattern\$3)) same ((oxygen or "O" or "O.sub.2") and (fluorine or fluoride or "F" or "F.sub.2" or ((nitrogen or "N" or "N.sub.2") and (hydrogen or "H"		
		magnetoresistive or magnetophotoresistive or (magneto adj photoresistive) or (giant adj magneto\$15) or (GMR same magneto\$15)).ti,ab.) and (resist or photoresist or photopolymer\$7 or photoimag\$5)) and ((ash\$3 or (ash adj treat\$4) or etch\$3 or narrow\$3 or shrink\$3 or shrunk\$3 or contract\$3 or small\$3 or littl\$3 or reduc\$3 or decreas\$3 or slim\$4 or trim\$4 or less\$5 or tight\$4) same (resist or photoresist or imag\$3 or pattern\$3))) and ((resist or photoresist or imag\$3 or pattern\$3))) and (fluorine or "O" or "O.sub.2") and (fluorine or fluoride or "F" or "F.sub.2" or ((nitrogen or "N" or "N.sub.2") and (hydrogen or "H" or "H.sub.2"))))) and (napthoquinonediazide or napthoquinonediazido)		
	37	magnetoresistive or magnetophotoresistive or (magneto adj photoresistive) or (giant adj magneto\$15) or (GMR same magneto\$15)).ti,ab.) and (resist or photoresist or photopolymer\$7 or photoimag\$5)) and ((ash\$3 or (ash adj treat\$4) or etch\$3 or narrow\$3 or shrink\$3 or shrunk\$3 or contract\$3 or small\$3 or littl\$3 or reduc\$3 or decreas\$3 or slim\$4 or trim\$4 or less\$5 or tight\$4) same (resist or photoresist or imag\$3 or pattern\$3))) and ((resist or photoresist or imag\$3 or pattern\$3))) and ((resist or photoresist or imag\$3 or pattern\$3) same ((oxygen or "O" or "O.sub.2") and (fluorine or fluoride or "F" or "F.sub.2" or ((nitrogen or "N" or "N.sub.2") and (hydrogen or "H" or "H.sub.2"))))) and (napthoquinonediazide or napthoquinonediazido) ((430/314,316,319-320,328-329).ccls. and	USPAT;	2004/08/09 18:10
	37	magnetoresistive or magnetophotoresistive or (magneto adj photoresistive) or (giant adj magneto\$15) or (GMR same magneto\$15)).ti,ab.) and (resist or photoresist or photopolymer\$7 or photoimag\$5)) and ((ash\$3 or (ash adj treat\$4) or etch\$3 or narrow\$3 or shrink\$3 or shrunk\$3 or contract\$3 or small\$3 or littl\$3 or reduc\$3 or decreas\$3 or slim\$4 or trim\$4 or less\$5 or tight\$4) same (resist or photoresist or imag\$3 or pattern\$3))) and ((resist or photoresist or imag\$3 or pattern\$3))) and ((resist or photoresist or imag\$3 or pattern\$3) same ((oxygen or "O" or "O.sub.2") and (fluorine or fluoride or "F" or "F.sub.2" or ((nitrogen or "N" or "N.sub.2") and (hydrogen or "H" or "H.sub.2"))))) and (napthoquinonediazide or napthoquinonediazido) ((430/314,316,319-320,328-329).ccls. and ((oxygen or "O.sub.2") same ((nitrogen or	USPAT; US-PGPUB;	2004/08/09 18:10
	37	magnetoresistive or magnetophotoresistive or (magneto adj photoresistive) or (giant adj magneto\$15) or (GMR same magneto\$15)).ti,ab.) and (resist or photoresist or photopolymer\$7 or photoimag\$5)) and ((ash\$3 or (ash adj treat\$4) or etch\$3 or narrow\$3 or shrink\$3 or shrunk\$3 or contract\$3 or small\$3 or littl\$3 or reduc\$3 or decreas\$3 or slim\$4 or trim\$4 or less\$5 or tight\$4) same (resist or photoresist or imag\$3 or pattern\$3)) and ((resist or photoresist or imag\$3 or pattern\$3)) and (fluorine or "O" or "O.sub.2") and (fluorine or fluoride or "F" or "F.sub.2" or ((nitrogen or "N" or "N.sub.2") and (hydrogen or "H" or "H.sub.2"))))) and (napthoquinonediazide or napthoquinonediazido) ((430/314,316,319-320,328-329).ccls. and ((oxygen or "O.sub.2") same ((nitrogen or "N.sub.2") and (hydrogen or "H.sub.2"))	US-PGPUB; EPO; JPO;	2004/08/09 18:10
	37	magnetoresistive or magnetophotoresistive or (magneto adj photoresistive) or (giant adj magneto\$15) or (GMR same magneto\$15)).ti,ab.) and (resist or photoresist or photopolymer\$7 or photoimag\$5)) and ((ash\$3 or (ash adj treat\$4) or etch\$3 or narrow\$3 or shrink\$3 or shrunk\$3 or contract\$3 or small\$3 or littl\$3 or reduc\$3 or decreas\$3 or slim\$4 or trim\$4 or less\$5 or tight\$4) same (resist or photoresist or imag\$3 or pattern\$3))) and ((resist or photoresist or imag\$3 or pattern\$3))) and ((resist or photoresist or imag\$3 or pattern\$3) same ((oxygen or "O" or "O.sub.2") and (fluorine or fluoride or "F" or "F.sub.2" or ((nitrogen or "N" or "N.sub.2") and (hydrogen or "H" or "H.sub.2"))))) and (napthoquinonediazide or napthoquinonediazido) ((430/314,316,319-320,328-329).ccls. and ((oxygen or "O.sub.2") same ((nitrogen or	US-PGPUB;	2004/08/09 18:10

		the state of the s		48
6	3	((resist or photoresist) and	USPAT;	2004/08/09 18:16
		(napthoquinonediazide or	US-PGPUB;	
		napthoquinonediazido)) and (novolac or	EPO; JPO;	
	0.50	novolak) and dissolution near3 accelerat\$3	IBM_TDB	
7	258	(430/328.ccls. and (heat\$3 or bak\$3) same	USPAT;	2004/08/09 18:19
		(expos\$3) same (develop\$3)) not	US-PGPUB;	
		(((430/314,316,319-320,328-329).ccls. and	EPO; JPO;	
1		((oxygen or "O.sub.2") same ((nitrogen or	IBM_TDB	
		"N.sub.2") and (hydrogen or "H.sub.2"))		
•		same (ash\$3 or etch\$3))) and (heat\$3 or		
		bak\$3) same (resist or photoresist))	j .	
8	4	(("5139904") or ("5747196") or ("6645677")	USPAT;	2004/08/09 18:24
		or ("20020187434")).PN.	US-PGPUB	
_	22	, , , , , , , , , , , , , , , , , , , ,	USPAT;	2003/03/18 16:46
		("5932396") or ("6480355") or ("5747198")	US-PGPUB	
		or ("6289578") or ("5725997") or		
		("6483664") or ("6501618") or ("6504678")		
		or ("20010010885") or ("20010019036") or		
		("20010027029") or ("6465149") or		
		("20010019465") or ("20010035355") or		
		("20010038517") or ("20010035343") or		
		("20020037476") or ("20020071211") or		
_	61272	("20030007295") or ("20020187430")).PN.	HODAE -	2002/02/03 17 50
-	61373	((magnetic adj head) or (magneto adj	ÚSPAT;	2003/03/07 17:59
-		resistive) or magnetoresistive or	US-PGPUB;	
1		magnetophotoresistive or (magneto adj	EPO; JPO;	
		photoresistive) or (giant adj magneto\$15) or (GMR same magneto\$15)).ti,ab.	IBM_TDB	
	2793		порад.	2002 (02 (07 10 00
-	2193	(((magnetic adj head) or (magneto adj resistive) or magnetoresistive or	USPAT;	2003/03/07 18:00
		magnetophotoresistive or (magneto adj	US-PGPUB;	<u> </u>
		photoresistive) or (giant adj magneto\$15)	EPO; JPO;	
		or (GMR same magneto\$15)).ti,ab.) and	IBM_TDB	
		(resist or photoresist or photopolymer\$7		1
		or photoimag\$5)		
	2003	((((magnetic adj head) or (magneto adj	II CDAM.	2002/02/07 10 07
· -	2003	resistive) or magnetoresistive or	USPAT;	2003/03/07 19:27
		magnetophotoresistive or (magneto adj	US-PGPUB; EPO; JPO;	
		photoresistive) or (giant adj magneto\$15)	IBM TDB	1
		or (GMR same magneto\$15)).ti,ab.) and	IBM_IDD	1
		(resist or photoresist or photopolymer\$7		i
		or photoimag\$5)) and ((ash\$3 or (ash adj		·
		treat\$4) or etch\$3 or narrow\$3 or shrink\$3		
		or shrunk\$3 or contract\$3 or small\$3 or		
		littl\$3 or reduc\$3 or decreas\$3 or slim\$4		
		or trim\$4 or less\$5 or tight\$4) same		'
		(resist or photoresist or imag\$3 or		· · · · · · · · · · · · · · · · · · ·
		pattern\$3))		
_	65	(((((magnetic adj head) or (magneto adj	USPAT;	2003/03/07 19:04
		resistive) or magnetoresistive or	US-PGPUB;	
		magnetophotoresistive or (magneto adj	EPO; JPO;	
		photoresistive) or (giant adj magneto\$15)	IBM TDB	
		or (GMR same magneto\$15)).ti,ab.) and		
		(resist or photoresist or photopolymer\$7		
		or photoimag\$5)) and ((ash\$3 or (ash adj		
		treat\$4) or etch\$3 or narrow\$3 or shrink\$3		
		or shrunk\$3 or contract\$3 or small\$3 or		
		littl\$3 or reduc\$3 or decreas\$3 or slim\$4		
		or trim\$4 or less\$5 or tight\$4) same	• .	
		(resist or photoresist or imag\$3 or		
		<pre>pattern\$3))) and ((resist or photoresist</pre>		
		or imag\$3 or pattern\$3) same ((oxygen or		
ĺ		"O" or "O.sub.2") and (fluorine or		
		fluoride or "F" or "F.sub.2" or ((nitrogen		
		or "N" or "N.sub.2") and (hydrogen or "H"		
		or "H.sub.2")))))		

[-	23	(((((((magnetic adj head) or (magneto adj	USPAT;	2004/04/09 20:07	٦
		resistive) or magnetoresistive or	US-PGPUB;	2001,01,03	
		magnetophotoresistive or (magneto adj	EPO; JPO;		
		photoresistive) or (giant adj magneto\$15)	IBM TDB		
		or (GMR same magneto\$15)).ti,ab.) and	1211_122		İ
		(resist or photoresist or photopolymer\$7			
		or photoimag\$5)) and ((ash\$3 or (ash adj			
		treat\$4) or etch\$3 or narrow\$3 or shrink\$3			
		or shrunk\$3 or contract\$3 or small\$3 or			
		littl\$3 or reduc\$3 or decreas\$3 or slim\$4			1
		or trim\$4 or less\$5 or tight\$4) same			
		(resist or photoresist or imag\$3 or			
		pattern\$3))) and ((resist or photoresist			
		or imag\$3 or pattern\$3) same ((oxygen or			
		"O" or "O.sub.2") and (fluorine or			
		fluoride or "F" or "F.sub.2" or ((nitrogen	1		ĺ
		or "N" or "N.sub.2") and (hydrogen or "H"			
		or "H.sub.2")))))) and (((mill\$3 or ion			ļ
		adj beam or FIB or RIE or ion adj etch\$3			
		or sputter\$3) or (lift adj off or liftoff			
	-	or remov\$3 or etchback or etch\$3 adj			
		back)) near5 (resist or photoresist or			
		imag\$3 or pattern\$3))) and ((heat\$3 or			İ
		bak\$3) with (resist or photoresist or		· ·	
		imag\$3 or pattern\$3))			l
_	56	((((((magnetic adj head) or (magneto adj	USPAT;	2003/03/07 19:02	
		resistive) or magnetoresistive or	US-PGPUB;		
		magnetophotoresistive or (magneto adj	EPO; JPO;		
		photoresistive) or (giant adj magneto\$15)	IBM TDB	· ·	İ
		or (GMR same magneto\$15)).ti.ab.) and			
		(resist or photoresist or photopolymer\$7			
		or photoimag\$5)) and ((ash\$3 or (ash adj			
		treat\$4) or etch\$3 or narrow\$3 or shrink\$3			
		or shrunk\$3 or contract\$3 or small\$3 or			
		littl\$3 or reduc\$3 or decreas\$3 or slim\$4			
		or trim\$4 or less\$5 or tight\$4) same			
		(resist or photoresist or imag\$3 or			
		pattern\$3))) and ((resist or photoresist			
		or imag\$3 or pattern\$3) same ((oxygen or		-	
		"O" or "O.sub.2") and (fluorine or			
		fluoride or "F" or "F.sub.2" or ((nitrogen			
		or "N" or "N.sub.2") and (hydrogen or "H"			
		or "H.sub.2")))))) and ((mill\$3 or ion			
		adj beam or FIB or RIE or ion adj etch\$3			
		or sputter\$3) or (lift adj off or liftoff			ŀ
		or remov\$3 or etchback or etch\$3 adj			
		back)) near5 (resist or photoresist or			
	1	imag\$3 or pattern\$3))			1

	33	((((((magnetic adj head) or (magneto adj	USPAT;	2004/04/09 20:06	٦
		resistive) or magnetoresistive or	US-PGPUB;		
		magnetophotoresistive or (magneto adj	EPO; JPO;		
		photoresistive) or (giant adj magneto\$15)	IBM TDB		1
		or (GMR same magneto\$15)).ti,ab.) and	_	•	Ì
		(resist or photoresist or photopolymer\$7			
ļ		or photoimag\$5)) and ((ash\$3 or (ash adj			
-		treat\$4) or etch\$3 or narrow\$3 or shrink\$3			
		or shrunk\$3 or contract\$3 or small\$3 or			
		littl\$3 or reduc\$3 or decreas\$3 or slim\$4			
ļ		or trim\$4 or less\$5 or tight\$4) same		1	
- 1		(resist or photoresist or imag\$3 or		1	
		pattern\$3))) and ((resist or photoresist			
		or imag\$3 or pattern\$3) same ((oxygen or			
		"O" or "O.sub.2") and (fluorine or			-
		fluoride or "F" or "F.sub.2" or ((nitrogen			
		or "N" or "N.sub.2") and (hydrogen or "H"			
		or "H.sub.2")))))) and (((mill\$3 or ion			
- 1		adj beam or FIB or RIE or ion adj etch\$3			ļ
		or sputter\$3) or (lift adj off or liftoff			
		or remov\$3 or etchback or etch\$3 adj			
ļ	į	back)) near5 (resist or photoresist or			
- 1		<pre>imag\$3 or pattern\$3))) not</pre>			ļ
		(((((((magnetic adj head) or (magneto adj		'	ı
-		resistive) or magnetoresistive or			1
		magnetophotoresistive or (magneto adj			
		photoresistive) or (giant adj magneto\$15)			-
		or (GMR same magneto\$15)).ti,ab.) and			l
		(resist or photoresist or photopolymer\$7			
-		or photoimag\$5)) and ((ash\$3 or (ash adj			1
		treat\$4) or etch\$3 or narrow\$3 or shrink\$3			-
	}	or shrunk\$3 or contract\$3 or small\$3 or			l
	•	littl\$3 or reduc\$3 or decreas\$3 or slim\$4			
1		or trim\$4 or less\$5 or tight\$4) same			
		(resist or photoresist or imag\$3 or			İ
-		<pre>pattern\$3))) and ((resist or photoresist</pre>			
1		or imag\$3 or pattern\$3) same ((oxygen or			
ļ		"O" or "O.sub.2") and (fluorine or			l
1	İ	fluoride or "F" or "F.sub.2" or ((nitrogen			l
		or "N" or "N.sub.2") and (hydrogen or "H"			l
	ļ	or "H.sub.2")))))) and (((mill\$3 or ion			
		adj beam or FIB or RIE or ion adj etch\$3			l
		or sputter\$3) or (lift adj off or liftoff			l
		or remov\$3 or etchback or etch\$3 adj			١
	ļ	back)) near5 (resist or photoresist or			
	İ	imag\$3 or pattern\$3))) and ((heat\$3 or			
		bak\$3) with (resist or photoresist or	•		ĺ
1		<pre>imag\$3 or pattern\$3)))</pre>			Ĺ

9 ((((((magnetic adj head) or (magneto adj resistive) or magnetoresistive or magnetophotoresistive or (magneto adj photoresistive) or (giant adj magneto\$15) photoresistive) or (giant adj magneto\$15) or (GMR same magneto\$15)).ti,ab.) and (resist or photoresist or photopolymer\$7 or photoimag\$5)) and ((ash\$3 or (ash adj treat\$4) or etch\$3 or narrow\$3 or shrink\$3 or shrunk\$3 or contract\$3 or small\$3 or littl\$3 or reduc\$3 or decreas\$3 or slim\$4 or trim\$4 or less\$5 or tight\$4) same (resist or photoresist or imag\$3 or pattern\$3))) and ((resist or photoresist	:57
magnetophotoresistive or (magneto adj photoresistive) or (giant adj magneto\$15) and (resist or photoresist or photopolymer\$7 or photoimag\$5)) and ((ash\$3 or (ash adj treat\$4) or etch\$3 or narrow\$3 or shrink\$3 or shrunk\$3 or shrunk\$3 or shrunk\$3 or contract\$3 or small\$3 or littl\$3 or reduc\$3 or decreas\$3 or slim\$4 or trim\$4 or less\$5 or tight\$4) same (resist or photoresist or imag\$3 or	
photoresistive) or (giant adj magneto\$15) or (GMR same magneto\$15)).ti,ab.) and (resist or photoresist or photopolymer\$7 or photoimag\$5)) and ((ash\$3 or (ash adj treat\$4) or etch\$3 or narrow\$3 or shrink\$3 or shrunk\$3 or contract\$3 or small\$3 or littl\$3 or reduc\$3 or decreas\$3 or slim\$4 or trim\$4 or less\$5 or tight\$4) same (resist or photoresist or imag\$3 or	
or (GMR same magneto\$15)).ti,ab.) and (resist or photoresist or photopolymer\$7 or photoimag\$5)) and ((ash\$3 or (ash adj treat\$4) or etch\$3 or narrow\$3 or shrink\$3 or shrunk\$3 or contract\$3 or small\$3 or littl\$3 or reduc\$3 or decreas\$3 or slim\$4 or trim\$4 or less\$5 or tight\$4) same (resist or photoresist or imag\$3 or	
(resist or photoresist or photopolymer\$7 or photoimag\$5)) and ((ash\$3 or (ash adj treat\$4) or etch\$3 or narrow\$3 or shrink\$3 or shrunk\$3 or contract\$3 or small\$3 or littl\$3 or reduc\$3 or decreas\$3 or slim\$4 or trim\$4 or less\$5 or tight\$4) same (resist or photoresist or imag\$3 or	
or photoimag\$5)) and ((ash\$3 or (ash adj treat\$4) or etch\$3 or narrow\$3 or shrink\$3 or shrunk\$3 or contract\$3 or small\$3 or littl\$3 or reduc\$3 or decreas\$3 or slim\$4 or trim\$4 or less\$5 or tight\$4) same (resist or photoresist or imag\$3 or	
treat\$4) or etch\$3 or narrow\$3 or shrink\$3 or shrunk\$3 or contract\$3 or small\$3 or littl\$3 or reduc\$3 or decreas\$3 or slim\$4 or trim\$4 or less\$5 or tight\$4) same (resist or photoresist or imag\$3 or	
or shrunk\$3 or contract\$3 or small\$3 or littl\$3 or reduc\$3 or decreas\$3 or slim\$4 or trim\$4 or less\$5 or tight\$4) same (resist or photoresist or imag\$3 or	
littl\$3 or reduc\$3 or decreas\$3 or slim\$4 or trim\$4 or less\$5 or tight\$4) same (resist or photoresist or imag\$3 or	į.
or trim\$4 or less\$5 or tight\$4) same (resist or photoresist or imag\$3 or	1
(resist or photoresist or imag\$3 or	
(resist or photoresist or imag\$3 or	
pattern\$3))) and ((resist or photoresist	
Facecaritalili and //rearac of buocofearac	Ì
or imag\$3 or pattern\$3) same ((oxygen or	
"O" or "O.sub.2") and (fluorine or	
fluoride or "F" or "F.sub.2" or ((nitrogen	
or "N" or "N.sub.2") and (hydrogen or "H"	
or "H.sub.2")))))) not ((((((magnetic adj	
head) or (magneto adj resistive) or	
magnetoresistive or magnetophotoresistive	1
or (magneto adj photoresistive) or (giant	
adj magneto\$15) or (GMR same	
magneto\$15)).ti,ab.) and (resist or	ļ
photoresist or photopolymer\$7 or	İ
photoimag\$5)) and ((ash\$3 or (ash adj	
treat\$4) or etch\$3 or narrow\$3 or shrink\$3	
or shrunk\$3 or contract\$3 or small\$3 or	
littl\$3 or reduc\$3 or decreas\$3 or slim\$4	
or trim\$4 or less\$5 or tight\$4) same	
(resist or photoresist or imag\$3 or	
pattern\$3))) and ((resist or photoresist	
or imag\$3 or pattern\$3) same ((oxygen or	
"O" or "O.sub.2") and (fluorine or	
fluoride or "F" or "F.sub.2" or ((nitrogen	.
or "N" or "N.sub.2") and (hydrogen or "H"	
or "H.sub.2")))))) and (((mill\$3 or ion	
adj beam or FIB or RIE or ion adj etch\$3	
or sputter\$3) or (lift adj off or liftoff	ļ
or remov\$3 or etchback or etch\$3 adj	1
back)) near5 (resist or photoresist or	
imag\$3 or pattern\$3)))	ļ

_	1938	(((((magnetic adj head) or (magneto adj	USPAT;	2003/03/18 16:14
		resistive) or magnetoresistive or	US-PGPUB;	
		magnetophotoresistive or (magneto adj	EPO; JPO;	
		photoresistive) or (giant adj magneto\$15)	IBM TDB	
		or (GMR same magneto\$15)).ti,ab.) and		
		(resist or photoresist or photopolymer\$7		
		or photoimag\$5)) and ((ash\$3 or (ash adj		
		treat\$4) or etch\$3 or narrow\$3 or shrink\$3		
		or shrunk\$3 or contract\$3 or small\$3 or		
	ļ	littl\$3 or reduc\$3 or decreas\$3 or slim\$4		
		or trim\$4 or less\$5 or tight\$4) same		
		(resist or photoresist or imag\$3 or		
		pattern\$3))) not (((((magnetic adj head)		
		or (magneto adj resistive) or		
		magnetoresistive or magnetophotoresistive	İ	
		,		
		or (magneto adj photoresistive) or (giant		
		adj magneto\$15) or (GMR same		
		magneto\$15)).ti,ab.) and (resist or		
		photoresist or photopolymer\$7 or		
		photoimag\$5)) and ((ash\$3 or (ash adj		
		treat\$4) or etch\$3 or narrow\$3 or shrink\$3]	
		or shrunk\$3 or contract\$3 or small\$3 or	1	
		littl\$3 or reduc\$3 or decreas\$3 or slim\$4		
		or trim\$4 or less\$5 or tight\$4) same		
		(resist or photoresist or imag\$3 or		
		pattern\$3))) and ((resist or photoresist		
		or imag\$3 or pattern\$3) same ((oxygen or		· ·
		"O" or "O.sub.2") and (fluorine or		
		fluoride or "F" or "F.sub.2" or ('(nitrogen		
	ĺ	or "N" or "N.sub.2") and (hydrogen or "H"		
		or "H.sub.2"))))))		
_	1	("5872693").PN.	USPAT;	2003/03/08 15:24
	_	(30/2033).111.	US-PGPUB	2003/03/08 13.24
İ	2	////maamakia adi baad\ a (2004/04/00 10 54
_	2	(((((magnetic adj head) or (magneto adj	USPAT;	2004/04/09 19:54
		resistive) or magnetoresistive or	US-PGPUB;	_
		magnetophotoresistive or (magneto adj	EPO; JPO;	
		photoresistive) or (giant adj magneto\$15)	IBM_TDB	
		or (GMR same magneto\$15)).ti,ab.) and	_	
		(resist or photoresist or photopolymer\$7		
İ		or photoimag\$5)) and ((ash\$3 or (ash adj		
		treat\$4) or etch\$3 or narrow\$3 or shrink\$3		
		or shrunk\$3 or contract\$3 or small\$3 or		
		littl\$3 or reduc\$3 or decreas\$3 or slim\$4		
ļ				<u> </u>
į		or trim\$4 or less\$5 or tight\$4) same		
		(resist or photoresist or imag\$3 or		
		<pre>pattern\$3))) not (((((magnetic adj head)</pre>		
		or (magneto adj resistive) or		
		magnetoresistive or magnetophotoresistive		
		or (magneto adj photoresistive) or (giant		
		adj magneto\$15) or (GMR same		
		magneto\$15)).ti,ab.) and (resist or		
ĺ		photoresist or photopolymer\$7 or		
		photoimag\$5)) and ((ash\$3 or (ash adj]
		treat\$4) or etch\$3 or narrow\$3 or shrink\$3		
		or shrunk\$3 or contract\$3 or small\$3 or		
		littl\$3 or reduc\$3 or decreas\$3 or slim\$4		
		or trim\$4 or less\$5 or tight\$4) same		•
		(resist or photoresist or imag\$3 or		
		pattern\$3))) and ((resist or photoresist		
		or imag\$3 or pattern\$3) same ((oxygen or		ļ
		"O" or "O.sub.2") and (fluorine or		į l
		fluoride or "F" or "F.sub.2" or ((nitrogen		
		or "N" or "N.sub.2") and (hydrogen or "H"		
		or "H.sub.2")))))) and		
		(polymethylglutarimide)		

-	0	(((((magnetic adj head) or (magneto adj	USPAT;	2004/04/09 19:47
		resistive) or magnetoresistive or magnetophotoresistive or (magneto adj	US-PGPUB; EPO; JPO;	
		photoresistive) or (giant adj magneto\$15)	IBM TDB	
		or (GMR same magneto\$15)).ti,ab.) and	_	
		(resist or photoresist or photopolymer\$7		
		or photoimag\$5)) and ((ash\$3 or (ash adj		
		treat\$4) or etch\$3 or narrow\$3 or shrink\$3 or shrunk\$3 or contract\$3 or small\$3 or		
		littl\$3 or reduc\$3 or decreas\$3 or slim\$4		
		or trim\$4 or less\$5 or tight\$4) same		
		(resist or photoresist or imag\$3 or		
		<pre>pattern\$3))) not (((((magnetic adj head) or (magneto adj resistive) or</pre>		
		magnetoresistive or magnetophotoresistive		
		or (magneto adj photoresistive) or (giant		
		adj magneto\$15) or (GMR same		
		magneto\$15)).ti,ab.) and (resist or photoresist or photopolymer\$7 or		
		photolesist of photopolymer, or photoimag\$5)) and ((ash\$3 or (ash adj		
		treat\$4) or etch\$3 or narrow\$3 or shrink\$3		
		or shrunk\$3 or contract\$3 or small\$3 or		
		littl\$3 or reduc\$3 or decreas\$3 or slim\$4 or trim\$4 or less\$5 or tight\$4) same		
		(resist or photoresist or imag\$3 or		
		pattern\$3))) and ((resist or photoresist		
		or imag\$3 or pattern\$3) same ((oxygen or		
		"O" or "O.sub.2") and (fluorine or fluoride or "F" or "F.sub.2" or ((nitrogen		
		or "N" or "N.sub.2") and (hydrogen or "H"		
		or "H.sub.2")))))) and		
		(napthoquinonediazide or		
	51	napthoquinonediazido) (resist or photoresist) and	USPAT;	2003/09/03 13:20
-	31	(napthoquinonediazide or	US-PGPUB;	2003/09/03 13:20
		napthoquinonediazido)	EPO; JPO;	
			IBM_TDB	
_	3	((resist or photoresist) and (napthoquinonediazide or	USPAT; US-PGPUB;	2003/09/03 13:25
	,	napthoquinonediazido)) and (novolac or	EPO; JPO;	
İ		novolak) and dissolution near3 accelerat\$3	IBM_TDB	
-	5	("4524121" "4745042" "5252831"	USPAT	2003/03/10 09:27
	45	"5604073" "5800963").PN. (430/314,316,319-320,328-329).ccls. and	HCDAT.	2003/03/10 15:51
	43	((oxygen or "0.sub.2") same ((nitrogen or	USPAT; US-PGPUB;	2003/03/10 15:51
		"N.sub.2") and (hydrogen or "H.sub.2"))	EPO; JPO;	
	0.5	same (ash\$3 or etch\$3))	IBM_TDB	
_	25	((430/314,316,319-320,328-329).ccls. and ((oxygen or "O.sub.2") same ((nitrogen or	USPAT; US-PGPUB;	2004/04/09 19:37
		"N.sub.2") and (hydrogen or "H.sub.2"))	EPO; JPO;	
		same (ash\$3 or etch\$3))) and (heat\$3 or	IBM_TDB	
	01.6	bak\$3) same (resist or photoresist)	Harra	
_	216	430/328.ccls. and (heat\$3 or bak\$3) same (expos\$3) same (develop\$3)	USPAT; US-PGPUB;	2003/03/10 17:38
		(enposts) same (developys)	EPO; JPO;	
			IBM_TDB	
-	211	(430/328.ccls. and (heat\$3 or bak\$3) same	USPAT;	2003/09/03 13:31
		(expos\$3) same (develop\$3)) not (((430/314,316,319-320,328-329).ccls. and	US-PGPUB; EPO; JPO;	
		((oxygen or "O.sub.2") same ((nitrogen or	IBM TDB	
		"N.sub.2") and (hydrogen or "H.sub.2"))		
		same (ash\$3 or etch\$3))) and (heat\$3 or		
_	3	bak\$3) same (resist or photoresist)) ("2922855").PN.	USPAT;	2003/09/03 13:52
		(222300)	US-PGPUB;	2003/03/03 13:32
			JPO;	
	l		DERWENT	

_	25	((((((magnetic adj head) or (magneto adj	USPAT;	2004/04/09 19:30
		resistive) or magnetoresistive or	US-PGPUB;	
		magnetophotoresistive or (magneto adj	EPO; JPO;	
		photoresistive) or (giant adj magneto\$15)	IBM_TDB	
•		or (GMR same magneto\$15)).ti,ab.) and		
		(resist or photoresist or photopolymer\$7 or photoimag\$5)) and ((ash\$3 or (ash adj		
	•	treat\$4) or etch\$3 or narrow\$3 or shrink\$3		
		or shrunk\$3 or contract\$3 or small\$3 or		
		littl\$3 or reduc\$3 or decreas\$3 or slim\$4		
		or trim\$4 or less\$5 or tight\$4) same		
		(resist or photoresist or imag\$3 or		
	İ	<pre>pattern\$3))) and ((resist or photoresist</pre>		
		or imag\$3 or pattern\$3) same ((oxygen or		
		"O" or "O.sub.2") and (fluorine or		
		fluoride or "F" or "F.sub.2" or ((nitrogen		
		or "N" or "N.sub.2") and (hydrogen or "H"		
		or "H.sub.2")))))) and (((mill\$3 or ion		
		adj beam or FIB or RIE or ion adj etch\$3		
		or sputter\$3) or (lift adj off or liftoff or remov\$3 or etchback or etch\$3 adj		
		back)) near5 (resist or photoresist or	1	
		imag\$3 or pattern\$3))) and ((heat\$3 or		
		bak\$3) with (resist or photoresist or		
		imag\$3 or pattern\$3))		
_	2	(((((magnetic adj head) or (magneto adj	USPAT;	2004/04/09 19:29
		resistive) or magnetoresistive or	US-PGPUB;	
		magnetophotoresistive or (magneto adj	EPO; JPO;	
		photoresistive) or (giant adj magneto\$15)	IBM_TDB	
		or (GMR same magneto\$15)).ti,ab.) and		
		(resist or photoresist or photopolymer\$7		i :
		or photoimag\$5)) and ((ash\$3 or (ash adj treat\$4) or etch\$3 or narrow\$3 or shrink\$3		
		or shrunk\$3 or contract\$3 or small\$3 or		
		littl\$3 or reduc\$3 or decreas\$3 or slim\$4		ļ
		or trim\$4 or less\$5 or tight\$4) same		
		(resist or photoresist or imag\$3 or		
		<pre>pattern\$3))) not (((((magnetic adj head)</pre>		
		or (magneto adj resistive) or		
	•	magnetoresistive or magnetophotoresistive		
		or (magneto adj photoresistive) or (giant		
		adj magneto\$15) or (GMR same		
		magneto\$15)).ti,ab.) and (resist or		
		photoresist or photopolymer\$7 or photoimag\$5)) and ((ash\$3 or (ash adj		
		treat\$4) or etch\$3 or narrow\$3 or shrink\$3		
		or shrunk\$3 or contract\$3 or small\$3 or		
		littl\$3 or reduc\$3 or decreas\$3 or slim\$4		
		or trim\$4 or less\$5 or tight\$4) same		
		(resist or photoresist or imag\$3 or		
		pattern\$3))) and ((resist or photoresist		
		or imag\$3 or pattern\$3) same ((oxygen or		
		"O" or "O.sub.2") and (fluorine or		
		fluoride or "F" or "F.sub.2" or ((nitrogen		
		or "N" or "N.sub.2") and (hydrogen or "H"		
		or "H.sub.2")))))) and (polymethylglutarimide)		
_	54	(resist or photoresist) and	USPAT;	2004/04/09 19:28
		(napthoquinonediazide or	US-PGPUB;	2004/04/09 19:28
		napthoquinonediazido)	EPO; JPO;	
		• • • • • • • • • • • • • • • • • • • •	IBM TDB	
_	3	((resist or photoresist) and	USPAT;	2004/04/09 19:28
		(napthoquinonediazide or	US-PGPUB;	
		napthoquinonediazido)) and (novolac or	EPO; JPO;	
		novolak) and dissolution near3 accelerat\$3	IBM_TDB	
_	32	((430/314,316,319-320,328-329).ccls. and	USPAT;	2004/04/09 19:26
		((oxygen or "0.sub.2") same ((nitrogen or "N sub.2") and (hydrogen or "W sub.2")	US-PGPUB;	
	ļ l	"N.sub.2") and (hydrogen or "H.sub.2")) same (ash\$3 or etch\$3))) and (heat\$3 or	EPO; JPO;	
		bak\$3) same (resist or photoresist)	IBM_TDB	
	<u> </u>	wantot pame (reproc or buorniegrae)		i l

	225	(430/328.ccls. and (heat\$3 or bak\$3) same (expos\$3) same (develop\$3)) not (((430/314,316,319-320,328-329).ccls. and ((oxygen or "0.sub.2") same ((nitrogen or "N.sub.2") and (hydrogen or "H.sub.2"))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/04/09 19:19
		same (ash\$3 or etch\$3))) and (heat\$3 or bak\$3) same (resist or photoresist))		
_	2	("5721078").PN.	USPAT; US-PGPUB; JPO;	2003/09/03 13:53
	244	(430/328.ccls. and (heat\$3 or bak\$3) same (expos\$3) same (develop\$3)) not (((430/314,316,319-320,328-329).ccls. and ((oxygen or "O.sub.2") same ((nitrogen or "N.sub.2") and (hydrogen or "H.sub.2")	DERWENT USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/08/09 18:18
_	33	same (ash\$3 or etch\$3))) and (heat\$3 or bak\$3) same (resist or photoresist)) ((430/314,316,319-320,328-329).ccls. and ((oxygen or "O.sub.2") same ((nitrogen or "N.sub.2") and (hydrogen or "H.sub.2")) same (ash\$3 or etch\$3))) and (heat\$3 or	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/04/09 19:26
-	3	bak\$3) same (resist or photoresist) ((resist or photoresist) and (napthoquinonediazide or napthoquinonediazido)) and (novolac or novolak) and dissolution near3 accelerat\$3	USPAT; US-PGPUB; EPO; JPO;	2004/08/09 18:16
	55	(resist or photoresist) and (napthoquinonediazide or napthoquinonediazido)	IBM_TDB USPAT; US-PGPUB; EPO; JPO; IBM TDB	2004/04/09 19:28
	4	(((((magnetic adj head) or (magneto adj resistive) or magnetoresistive or magnetophotoresistive or (magneto adj photoresistive) or (giant adj magneto\$15) or (GMR same magneto\$15)).ti,ab.) and (resist or photoresist or photopolymer\$7 or photoimag\$5)) and ((ash\$3 or (ash adj treat\$4) or etch\$3 or narrow\$3 or shrink\$3 or shrunk\$3 or scontract\$3 or small\$3 or littl\$3 or reduc\$3 or decreas\$3 or slim\$4 or trim\$4 or less\$5 or tight\$4) same (resist or photoresist or imag\$3 or pattern\$3))) not (((((magnetic adj head) or (magneto adj resistive) or magnetoresistive or magnetophotoresistive or (magneto adj photoresistive) or (giant adj magneto\$15)) or (GMR same magneto\$15)).ti,ab.) and (resist or photoresist or photopolymer\$7 or photoimag\$5)) and ((ash\$3 or (ash adj treat\$4) or etch\$3 or narrow\$3 or shrink\$3 or shrunk\$3 or contract\$3 or small\$3 or littl\$3 or reduc\$3 or decreas\$3 or slim\$4 or trim\$4 or less\$5 or tight\$4) same (resist or photoresist or imag\$3 or pattern\$3)) and ((resist or photoresist or imag\$3 or pattern\$3)) and (fluorine or fluoride or "F" or "F.sub.2" or ((nitrogen or "N" or "N.sub.2") and (hydrogen or "H" or "H.sub.2")))))) and (polymethylglutarimide)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/04/09 19:29

-	31	((((((magnetic adj head) or (magneto adj	USPAT;	2004/04/09 19:31
		resistive) or magnetoresistive or	US-PGPUB;	
		magnetophotoresistive or (magneto adj	EPO; JPO;	
		photoresistive) or (giant adj magneto\$15)	IBM TDB	
		or (GMR same magneto\$15)).ti,ab.) and	_	
1		(resist or photoresist or photopolymer\$7		
		or photoimag\$5)) and ((ash\$3 or (ash adj		
		treat\$4) or etch\$3 or narrow\$3 or shrink\$3		
		or shrunk\$3 or contract\$3 or small\$3 or		
		littl\$3 or reduc\$3 or decreas\$3 or slim\$4		
		or trim\$4 or less\$5 or tight\$4) same		
		(resist or photoresist or imag\$3 or		
	İ	pattern\$3))) and ((resist or photoresist		·
		or image? or nottenness of photoresist		
		or imag\$3 or pattern\$3) same ((oxygen or		
		"O" or "O.sub.2") and (fluorine or		
		fluoride or "F" or "F.sub.2" or ((nitrogen		
		or "N" or "N.sub.2") and (hydrogen or "H"		
		or "H.sub.2")))))) and (((mill\$3 or ion		
		adj beam or FIB or RIE or ion adj etch\$3		
		or sputter\$3) or (lift adj off or liftoff		
		or remov\$3 or etchback or etch\$3 adj		
		back)) near5 (resist or photoresist or		
		imag\$3 or pattern\$3))) and ((heat\$3 or	ļ	
		bak\$3) with (resist or photoresist or		
		imag\$3 or pattern\$3))		
-	33	((430/314,316,319-320,328-329).ccls. and	USPAT;	2004/08/09 18:10
		((oxygen or "O.sub.2") same ((nitrogen or	US-PGPUB;	2001,00,00 10.10
		"N.sub.2") and (hydrogen or "H.sub.2"))	EPO; JPO;	
		same (ash\$3 or etch\$3))) and (heat\$3 or	IBM TDB	
		bak\$3) same (resist or photoresist)	TDIT_TDD	
_	0	(((((magnetic adj head) or (magneto adj	USPAT;	2004/08/09 18:10
		resistive) or magnetoresistive or	· ·	2004/08/09 18:10
			US-PGPUB;	
	Ì	magnetophotoresistive or (magneto adj	EPO; JPO;	
		photoresistive) or (giant adj magneto\$15)	IBM_TDB	
		or (GMR same magneto\$15)).ti,ab.) and		
		(resist or photoresist or photopolymer\$7		
		or photoimag\$5)) and ((ash\$3 or (ash adj		
	į	treat\$4) or etch\$3 or narrow\$3 or shrink\$3		
		or shrunk\$3 or contract\$3 or small\$3 or		
		littl\$3 or reduc\$3 or decreas\$3 or slim\$4		
		or trim\$4 or less\$5 or tight\$4) same		
		(resist or photoresist or imag\$3 or	·	
		<pre>pattern\$3))) not (((((magnetic adj head)</pre>		
		or (magneto adj resistive) or		
		magnetoresistive or magnetophotoresistive		S. C. C. C. C. C. C. C. C. C. C. C. C. C.
		or (magneto adj photoresistive) or (giant		
		adj magneto\$15) or (GMR same		
		magneto\$15)).ti,ab.) and (resist or		
		photoresist or photopolymer\$7 or		,
		photoimag\$5)) and ((ash\$3 or (ash adj		
		treat\$4) or etch\$3 or narrow\$3 or shrink\$3		
		or shrunk\$3 or contract\$3 or small\$3 or		
		littl\$3 or reduc\$3 or decreas\$3 or slim\$4		
		or trim\$4 or less\$5 or tight\$4) same		
	[(resist or photoresist or imag\$3 or		
		pattern\$3))) and ((resist or photoresist		
		or imag\$3 or pattern\$3) same ((oxygen or		
!		"O" or "O.sub.2") and (fluorine or		
		fluoride or "F" or "F.sub.2" or ((nitrogen		
		or "N" or "N.sub.2") and (hydrogen or "H"		
]	or "H.sub.2")))))) and		
	j	(napthoquinonediazide or		
	1	napthoquinonediazido)		

_	4	(((((magnetic adj head) or (magneto adj	USPAT;	2004/08/09 18:08
		resistive) or magnetoresistive or	US-PGPUB;	
		magnetophotoresistive or (magneto adj	EPO; JPO;	
		photoresistive) or (giant adj magneto\$15)	IBM TDB	
		or (GMR same magneto\$15)).ti,ab.) and	_	
		(resist or photoresist or photopolymer\$7		
		or photoimag\$5)) and ((ash\$3 or (ash adj		
		treat\$4) or etch\$3 or narrow\$3 or shrink\$3		
		or shrunk\$3 or contract\$3 or small\$3 or		
	ļ	littl\$3 or reduc\$3 or decreas\$3 or slim\$4		
		or trim\$4 or less\$5 or tight\$4) same		
		(resist or photoresist or imag\$3 or		
		<pre>pattern\$3))) not (((((magnetic adj head)</pre>	Į	
		or (magneto adj resistive) or		
		magnetoresistive or magnetophotoresistive		İ
		or (magneto adj photoresistive) or (giant		
		adj magneto\$15) or (GMR same		
		magneto\$15)).ti,ab.) and (resist or		
		photoresist or photopolymer\$7 or		
		photoimag\$5)) and ((ash\$3 or (ash adj		
		treat\$4) or etch\$3 or narrow\$3 or shrink\$3		
•		or shrunk\$3 or contract\$3 or small\$3 or		ł
		littl\$3 or reduc\$3 or decreas\$3 or slim\$4		
		or trim\$4 or less\$5 or tight\$4) same		_
		(resist or photoresist or imag\$3 or		
		pattern\$3))) and ((resist or photoresist		
		or imag\$3 or pattern\$3) same ((oxygen or		
		"O" or "O.sub.2") and (fluorine or		
		fluoride or "F" or "F.sub.2" or ((nitrogen		
		or "N" or "N.sub.2") and (hydrogen or "H"		
		or "H.sub.2")))))) and		
		(polymethylglutarimide)		

			4	
T	11	(((((magnetic adj head) or (magneto adj	USPAT;	2004/08/09 18:07
		resistive) or magnetoresistive or	US-PGPUB;	
		magnetophotoresistive or (magneto adj	EPO; JPO;	
		photoresistive) or (giant adj magneto\$15)	IBM_TDB	
		or (GMR same magneto\$15)).ti,ab.) and		
		(resist or photoresist or photopolymer\$7		
		or photoimag\$5)) and ((ash\$3 or (ash adj		
		treat\$4) or etch\$3 or narrow\$3 or shrink\$3		
		or shrunk\$3 or contract\$3 or small\$3 or		
		litt1\$3 or reduc\$3 or decreas\$3 or slim\$4		
÷		or trim\$4 or less\$5 or tight\$4) same		•
		(resist or photoresist or imag\$3 or		
		pattern\$3))) and ((resist or photoresist		
		or imag\$3 or pattern\$3) same ((oxygen or		
		"O" or "O.sub.2") and (fluorine or		
		fluoride or "F" or "F.sub.2" or ((nitrogen		
		or "N" or "N.sub.2") and (hydrogen or "H"		
		or "H.sub.2")))))) not ((((((magnetic adj		
		head) or (magneto adj resistive) or		•
		magnetoresistive or magnetophotoresistive		
		or (magneto adj photoresistive) or (giant		
		adj magneto\$15) or (GMR same		
		magneto\$15)).ti,ab.) and (resist or		
		photoresist or photopolymer\$7 or		
		photoimag\$5)) and ((ash\$3 or (ash adj		
		treat\$4) or etch\$3 or narrow\$3 or shrink\$3		
		or shrunk\$3 or contract\$3 or small\$3 or		
		littl\$3 or reduc\$3 or decreas\$3 or slim\$4		
		or trim\$4 or less\$5 or tight\$4) same		
		(resist or photoresist or imag\$3 or		
		pattern\$3))) and ((resist or photoresist		
		or imag\$3 or pattern\$3) same ((oxygen or		
		"O" or "O.sub.2") and (fluorine or		
		fluoride or "F" or "F.sub.2" or ((nitrogen		
		or "N" or "N.sub.2") and (hydrogen or "H"		
		or "H.sub.2")))))) and (((mill\$3 or ion		
		adj beam or FIB or RIE or ion adj etch\$3		
		or sputter\$3) or (lift adj off or liftoff		
		or remov\$3 or etchback or etch\$3 adj		
		back)) near5 (resist or photoresist or		
		imag\$3 or pattern\$3)))	USPAT;	2004/08/09 18:06
-	31	(((((((magnetic adj head) or (magneto adj	US-PGPUB;	2004/00/09 10:00
		resistive) or magnetoresistive or	EPO; JPO;	
		magnetophotoresistive or (magneto adj	IBM TDB	
		photoresistive) or (giant adj magneto\$15)	1 100	
		or (GMR same magneto\$15)).ti,ab.) and		
		(resist or photoresist or photopolymer\$7 or photoimag\$5)) and ((ash\$3 or (ash adj		
		treat\$4) or etch\$3 or narrow\$3 or shrink\$3	1	
-		or shrunk\$3 or contract\$3 or small\$3 or		
		littl\$3 or reduc\$3 or decreas\$3 or slim\$4		,
		or trim\$4 or less\$5 or tight\$4) same		
		(resist or photoresist or imag\$3 or		
		pattern\$3))) and ((resist or photoresist		
		or imag\$3 or pattern\$3) same ((oxygen or "O" or "O.sub.2") and (fluorine or		
		fluoride or "F" or "F.sub.2" or ((nitrogen		
		or "N" or "N.sub.2") and (hydrogen or "H"		
		or "H.sub.2")))))) and ((mill\$3 or ion		
			1	
		adj beam or FIB or RIE or ion adj etch\$3		
		or sputter\$3) or (lift adj off or liftoff		
		or remov\$3 or etchback or etch\$3 adj		,
		back)) near5 (resist or photoresist or imag\$3 or pattern\$3))) and ((heat\$3 or		
		bak\$3) with (resist or photoresist or		
		imag\$3 or pattern\$3))		
L		Imagys of paccernys//	1	1